

Title (en)

LITHOGRAPHIC SCANNING EXPOSURE PROJECTION APPARATUS

Title (de)

LITHOGRAPHISCHER PROJEKTIONSSAPPARAT ZUR ABTASTBELICHTUNG

Title (fr)

INSOLATRICE LITHOGRAPHIQUE A EXPOSITION PAR BALAYAGE

Publication

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Application

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Priority

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Abstract (en)

[origin: WO9737283A1] A lithographic scanning exposure projection apparatus is provided with a radiation source (1) providing radiation pulses, a lens system (3, 7), a mask (5), imaged onto a substrate (9) and scanning means (10) for scanning an image of an exit window (2) of the radiation source at a scanning speed over the substrate (9). A controller (13) controls both the energy of the radiation pulses and the scanning speed in dependence on the required exposure dose on the substrate and the repetition rate of the radiation pulses. The controller ensures maximum throughput of substrates through the apparatus and a minimum dose non-uniformity on the substrates.

IPC 1-7

G03F 7/20

IPC 8 full level

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